L' represents a single bond or an (n'+1) valent linking group,

Y' represents an alicyclic group, and

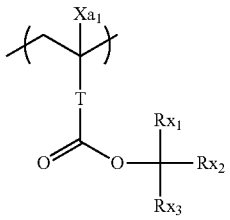
n' represents an integer of 1 or more.

2. The pattern forming method according to claim **1**, wherein the exposing in (ii) is exposing using the KrF excimer laser.

3. The pattern forming method according to claim **1**, wherein in the general formula (1), L represents a single bond, an alkylene group, an aromatic ring group, a cycloalkylene group, —COO-L_1'-, —O-L_1'-, —CONH—, or a group which is formed by combining two or more of these, L_1' represents an alkylene group, a cycloalkylene group, an aromatic ring group, or a group formed by combining an alkylene group and an aromatic ring group.

4. The pattern forming method according to claim **1**, wherein the resin (A) comprises a repeating unit which is represented by the following general formula (AI) as the repeating unit including a group capable of generating a polar group by being decomposed due to an action of an acid:

(AI)



in the general formula (AI),

Xa_1 represents a hydrogen atom, an alkyl group, a cyano group, or a halogen atom,

T represents a single bond or a divalent linking group,

Rx_1 to Rx_3 each independently represents an alkyl group or a cycloalkyl group, and

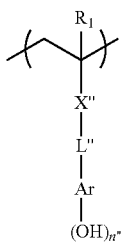
two among Rx_1 to Rx_3 may be bonded to form a ring structure.

5. The pattern forming method according to claim **4**, wherein R_{X1} to R_{X3} in the general formula (AI) represent an alkyl group.

6. The pattern forming method according to claim **4**, wherein R_{X1} to R_{X3} in the general formula (AI) represent a methyl group.

7. The pattern forming method according to claim **1**, wherein the repeating unit which is represented by the general formula (1) is a repeating unit which is represented by the following general formula (1-1):

(1-1)



in the general formula (1-1),

R_1 represents a hydrogen atom, an alkyl group, a halogen atom, or an alkoxycarbonyl group,

X" represents a single bond, an alkylene group, —COO—, or —$CONR_{64}$—,

R_{64} represents a hydrogen atom or an alkyl group,

L" represents a single bond, —COO—, or an alkylene group,

Ar represents an (n"+1) valent aromatic ring group, and

n" represents an integer of 1 to 4.

8. A method for manufacturing an electronic device which includes the pattern forming method according to claim **1**.

9. The pattern forming method according to claim **1**, wherein in the general formula (1'), L' represents a single bond, an alkylene group, an aromatic ring group, a cycloalkylene group, —COO-L_1'-, —O-L_1'-, —CONH—, or a group which is formed by combining two or more of these, L_1' represents an alkylene group, a cycloalkylene group, an aromatic ring group, or a group formed by combining an alkylene group and an aromatic ring group.

10. An actinic ray-sensitive or radiation-sensitive resin composition which is subjected to a pattern forming method comprising

(i) forming a film using the actinic ray-sensitive or radiation-sensitive resin composition,

(ii) exposing the film using a KrF excimer laser, extreme ultraviolet rays, or an electron beam, and

(iii) forming a negative tone pattern by developing the exposed film using a developer which includes an organic solvent,

the actinic ray-sensitive or radiation-sensitive resin composition comprising:

a resin (A) which has a repeating unit including

a group capable of generating a polar group by being decomposed due to an action of an acid,

a repeating unit including a carboxyl group, and a repeating unit including a lactone structure, and the content of the repeating unit including the lactone structure is greater than 0 mol % and less than or equal to 10 mol % with respect to all the repeating units in the resin (A);

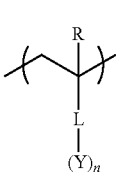
a non-acid-decomposable repeating unit which is represented by the following general formula (1), which is different from the repeating unit including a carboxyl group,

a non-acid-decomposable repeating unit which is represented by the following general formula (1'), which is different from the repeating unit including a carboxyl group;

a compound (B) which generates an acid according to irradiation with actinic rays or radiation; and

a solvent (C),

(1)



in the general formula (1),

R represents a hydrogen atom, an alkyl group, a cycloalkyl group, a halogen atom, or an alkoxycarbonyl group,